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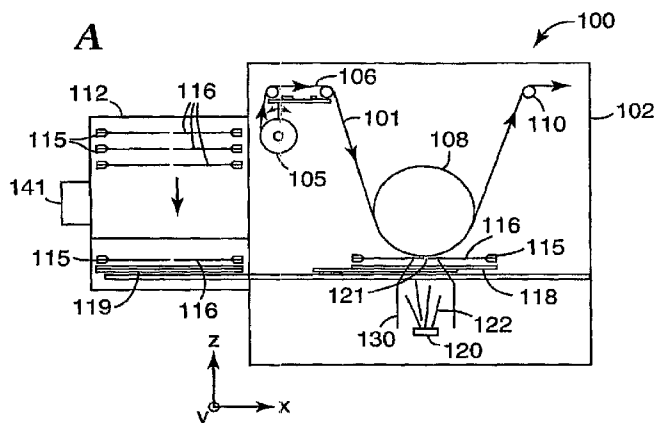
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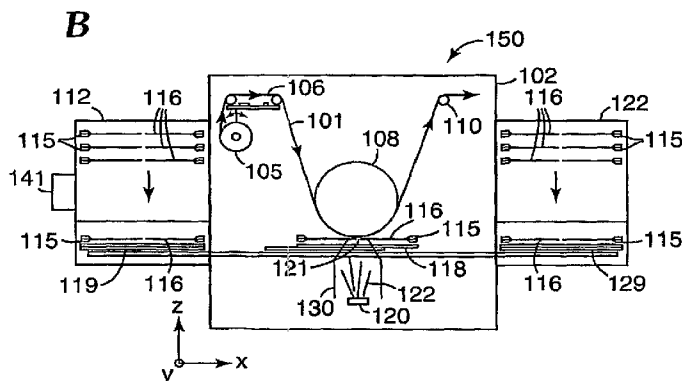
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(54) Title: RECIPROCATING APERTURE MASK SYSTEM AND METHOD



(57) Abstract: An apparatus for depositing a pattern of material on a substrate includes reciprocating aperture mask. A feed magazine houses a plurality of jigs, each of the jigs configured to support a mask having apertures defining a pattern. A shuttle mechanism receives a selected jig presented by the feed magazine and establishes contact between the mask of the selected jig and the substrate. The shuttle mechanism moves the selected jig in line with the substrate and relative to the deposition source so that deposition material passes through the apertures of the mask of the selected jig to develop the pattern of the deposition material on the substrate.





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